

This article was downloaded by:

On: 28 January 2011

Access details: *Access Details: Free Access*

Publisher *Taylor & Francis*

Informa Ltd Registered in England and Wales Registered Number: 1072954 Registered office: Mortimer House, 37-41 Mortimer Street, London W1T 3JH, UK



Physics and Chemistry of Liquids

Publication details, including instructions for authors and subscription information:

<http://www.informaworld.com/smpp/title~content=t713646857>

Editorial board page for “Physics and Chemistry of Liquids”, Volume 20, Number 2-3

To cite this Article (1989) 'Editorial board page for “Physics and Chemistry of Liquids”, Volume 20, Number 2-3', Physics and Chemistry of Liquids, 20: 2, a

To link to this Article: DOI: 10.1080/00319108908036391

URL: <http://dx.doi.org/10.1080/00319108908036391>

PLEASE SCROLL DOWN FOR ARTICLE

Full terms and conditions of use: <http://www.informaworld.com/terms-and-conditions-of-access.pdf>

This article may be used for research, teaching and private study purposes. Any substantial or systematic reproduction, re-distribution, re-selling, loan or sub-licensing, systematic supply or distribution in any form to anyone is expressly forbidden.

The publisher does not give any warranty express or implied or make any representation that the contents will be complete or accurate or up to date. The accuracy of any instructions, formulae and drug doses should be independently verified with primary sources. The publisher shall not be liable for any loss, actions, claims, proceedings, demand or costs or damages whatsoever or howsoever caused arising directly or indirectly in connection with or arising out of the use of this material.

PHYSICS AND CHEMISTRY OF LIQUIDS
AN INTERNATIONAL JOURNAL

N. H. MARCH *Editor*

Department of Theoretical Chemistry, 5 South Parks Road, Oxford, OX1 3UB, UK

EDITORIAL ADVISORY BOARD

C. F. CURTISS

*University of Wisconsin, Madison, Wisconsin,
USA*

N. E. CUSACK

University of East Anglia, Norwich, England, UK

P. A. EGELSTAFF

University of Guelph, Guelph, Ontario, Canada

H. ENDO

University of Kyoto, Kyoto, Japan

J. FRIEDEL

University of Paris, Orsay, France

K. E. LARSSON

Royal Institute of Technology, Stockholm, Sweden

M. MANDEL

Rijksuniversiteit te Leiden, Leiden, The Netherlands

N. H. NACHTRIEB

University of Chicago, Chicago, Illinois, USA

D. W. OXTOBY

University of Chicago, Chicago, Illinois, USA

I. PRIGOGINE

*Faculté des Sciences, Bruxelles, 1050 Belgium
and University of Texas, Austin, Texas, USA*

R. L. SCOTT

*University of California, Los Angeles, California,
USA*

S. STEEB

*Max Planck Institut für Metallforschung,
Stuttgart, FRG*

N. J. TRAPPENIERS

*Universiteit van Amsterdam, Amsterdam,
The Netherlands*